

**REMARKS**

This paper is filed in response to the Office Action mailed on October 20, 2004. In the Office Action, claims 1-6 stand rejected; claims 7-17 are allowed. In response, claims 1 and 3 have been amended to traverse the rejections thereby placing this application in a condition for allowance. Claim 13 has also been amended to correct an informality.

Turning to the rejections based upon the prior art, the Patent Office rejects claims 1 and 2 under 35 U.S.C. §102(b) as allegedly being anticipated by U.S. Patent No. 3,297,663 ("Herbst"). In response, claims 1 and 2 have been amended to traverse this rejection. Specifically, Herbst merely discloses a vinylphosphonic acid homopolymer for use as a plastic. Herbst in no way teaches or suggests this polymer or related polymers for use as an organic anti-reflective coating composition. Accordingly, claim 1 has been amended to recite a method of forming a pattern on a semiconductor device that comprises coating a photoresist film on a semiconductor substrate, applying the organic anti-reflective coating polymer of claim 1 on top of the photoresist film and then exposing and developing the photo with resist film. Herbst in no way teaches or suggests this method and therefore amended claims 1 and 2 are clearly not anticipated by Herbst. An early withdrawal of the rejection of claims 1 and 2 as being anticipated by Herbst is earnestly solicited.

Next, claims 3-6 stand rejected under 35 U.S.C. §103 as being unpatentable over Herbst. In response, claim 3 has been amended to clearly traverse this rejection. Claim 3 now depends from allowable claim 1 which is directed toward a method for forming a pattern on a semiconductor substrate using an organic anti-reflective coating composition that comprises the polymer of Formula I. Because claim 1 is clearly allowable over Herbst, claim 3 is clearly allowable as well. Herbst in no way teaches or suggests the use of any of its polymers disclosed therein for use as organic anti-reflective coatings and in no way teaches or suggests the use of any polymer as an anti-reflective coating. Herbst only teaches the use of its polymers for "the manufacture of shaped articles." Herbst also teaches the use of its polymers as "plastics," but this definition clearly does not encompass organic anti-reflective coatings. Further, no prior art reference teaches or suggests the use of any polymer of example 19 of Herbst for use in the semiconductor industry.

Accordingly, amended claim 3 is clearly allowable over Herbst and Applicants respectfully request that the rejection of claims 3-6 be withdrawn.

An early action indicating the allowability of this application is earnestly solicited.

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Respectfully submitted,

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